ELSEVIER

Thin Solid Films 365 (2000) 376–377

thin solid films

www.elsevier.com/locate/tsf

Author Index of Volume 365

Adams, J.B., 201
Alford, T., 19
Alves, O.L., 90
Ayllón, J.A., 12

Balakrishnan, K.S., 322
Baumann, F., 189
Beckers, M., 82
Berg, S., 43
Bernard, C., 264
Blanquet, E., 264
Block, B.A., 126
Borucki, L., 211
Borucki, L.J., 152, 368
Buss, R.J., 251

Cale, T.S., 152, 368
Cao, L., 129
Cao, Y., 49
Caturla, M.J., 219
Chan, Y.C., 77
Chen, D.H., 53
Chen, J.Z., 61
Chen, L., 94
Chen, Y.S., 61
Cheng, S.D., 77
Cho, J.-S., 5
Chung, P.L., 72
Coltrin, M.E., 251
Cui, H., 129

Dalla Torre, J., 189
Damodaran, S., 99
Das, B., 1
Daube, C., 139
de la Rubia, T.D., 189
Diaz de la Rubia, T., 219
Dimitrova, V., 134
Dobrowolska, M., 1
Domènech, X., 12

Economou, D.J.,348
Ederth, J., 119
Edgar, T.F., 322
Espinoza-Beltrán, F.J., 30

Feng, L., 99
Ford, G.M., 126

Gómez, M., 119
Galembeck, A., 90
Gan, W.S., 77
García-Cerda, L.A., 30
Gill, D.M., 126
Gilmer, G.H., 189
Gobbert, M.K., 368
González-Hernández, J., 30
Goorsky, M.S., 147
Granqvist, C.G., 119

Han, X.Q., 77
Hlavacek, V., 275
Ho, P., 251, 334
Ho, S.T., 126
Hong, L.-S., 176
Hong, S.G., 58
Hrubý, H., 104
Hu, X., 49
Huang, H., 189
Huang, J.S., 110
Huilin, Z., 67
Huo, L., 129

Jawad, Z.S., 19
Jensen, K.F., 231
Jiang, D., 129
Jiang, Y., 116
Johnson, M.D., 219
Jonsson, L.B., 43

Kam, C.H., 77
Katardjiev, I., 43
Kersch, A., 307
Kim, C.J., 58
Kim, S.-S., 126
Klöppel, A., 139
Kleijn, C.R., 294
Komjyama, H., 176
Kondo, W., 36
Kriegseis, W., 139
Kumagai, T., 36

Labun, A.H., 152
Lam, Y.L., 77
Lange, T., 82
Lee, M.-H., 5
Lei, Y.M., 53
Lengyel, I., 231
Lenosky, T., 219
Li, C., 94
Li, W., 129
Li, X., 129
Li, Y., 201
Liu, C.-L., 211
Liu, X., 116
Lu, X., 116
Lui, X., 94

Madar, R., 264
Makhviladze, T.M., 211
Manabe, T., 36
Manzanares-Martínez, J., 30
McGinnis, S.P., 1
Meeks, E., 334
Merchant, T.P., 152, 368
Metzger, R., 242
Meyer, B.K., 139
Mizuta, S., 36
Moffat, H.K., 251
Musil, J., 104

Niklasson, G.A., 119
Njoroge, W., 82
Nyberg, T., 43

Oates, A.S., 110
Oh, J.T., 77
Olowolafe, J.O., 19

Pérez-Robles, J.F., 30
Park, G.-S., 7
Pingsheng, H., 67
Pons, M., 264

Que, W.X., 77

Ramírez-Bon, R., 30

Rau, I., 19
Ren, C.X., 53
Rodríguez, J., 119
Rodríguez-Clemente, R., 12

Saadoun, L., 12
Sadigh, B., 219
Sarychev, M.E., 211
Schafbauer, T., 307
Scharmann, A., 139
Shimogaki, Y., 176
Spitzer, A., 242
Stollenwerk, J., 139
Swann, C.P., 19

Tate, J., 134
Theiss, S.K., 219
Thiart, J.J., 275
Tian, J., 49
Trube, J., 139
Tsai, C.J., 72

Unruh, K.M., 19
U'Ren, G.D., 147
Usui, H., 22

Vigil, E., 12
Viljoen, H.J., 275

Wang, G., 116
Wang, H., 94
Wang, K.L., 147
Wang, W., 116
Wang, X., 94
Wang, Z., 201
Weihua, G., 67
Weis, H., 82
Weixing, L., 67
Werner, C., 242
Wessels, B.W., 126
Wilson, I.H., 53
Wong, S.P., 53
Wu, S.K., 61
Wuttig, M., 82

PII: S0040-6090(00)00929-9

ELSEVIER

Thin Solid Films 365 (2000) 376–377

thin solid films

www.elsevier.com/locate/tsf

Author Index of Volume 365

Adams, J.B., 201
Alford, T., 19
Alves, O.L., 90
Ayllón, J.A., 12

Balakrishnan, K.S., 322
Baumann, F., 189
Beckers, M., 82
Berg, S., 43
Bernard, C., 264
Blanquet, E., 264
Block, B.A., 126
Borucki, L., 211
Borucki, L.J., 152, 368
Buss, R.J., 251

Cale, T.S., 152, 368
Cao, L., 129
Cao, Y., 49
Caturla, M.J., 219
Chan, Y.C., 77
Chen, D.H., 53
Chen, J.Z., 61
Chen, L., 94
Chen, Y.S., 61
Cheng, S.D., 77
Cho, J.-S., 5
Chung, P.L., 72
Coltrin, M.E., 251
Cui, H., 129

Dalla Torre, J., 189
Damodaran, S., 99
Das, B., 1
Daube, C., 139
de la Rubia, T.D., 189
Diaz de la Rubia, T., 219
Dimitrova, V., 134
Dobrowolska, M., 1
Domènech, X., 12

Economou, D.J.,348
Ederth, J., 119
Edgar, T.F., 322
Espinoza-Beltrán, F.J., 30

Feng, L., 99
Ford, G.M., 126

Gómez, M., 119
Galembeck, A., 90
Gan, W.S., 77
García-Cerda, L.A., 30
Gill, D.M., 126
Gilmer, G.H., 189
Gobbert, M.K., 368
González-Hernández, J., 30
Goorsky, M.S., 147
Granqvist, C.G., 119

Han, X.Q., 77
Hlavacek, V., 275
Ho, P., 251, 334
Ho, S.T., 126
Hong, L.-S., 176
Hong, S.G., 58
Hrubý, H., 104
Hu, X., 49
Huang, H., 189
Huang, J.S., 110
Huilin, Z., 67
Huo, L., 129

Jawad, Z.S., 19
Jensen, K.F., 231
Jiang, D., 129
Jiang, Y., 116
Johnson, M.D., 219
Jonsson, L.B., 43

Kam, C.H., 77
Katardjiev, I., 43
Kersch, A., 307
Kim, C.J., 58
Kim, S.-S., 126
Klöppel, A., 139
Kleijn, C.R., 294
Komjyama, H., 176
Kondo, W., 36
Kriegseis, W., 139
Kumagai, T., 36

Labun, A.H., 152
Lam, Y.L., 77
Lange, T., 82
Lee, M.-H., 5
Lei, Y.M., 53
Lengyel, I., 231
Lenosky, T., 219
Li, C., 94
Li, W., 129
Li, X., 129
Li, Y., 201
Liu, C.-L., 211
Liu, X., 116
Lu, X., 116
Lui, X., 94

Madar, R., 264
Makhviladze, T.M., 211
Manabe, T., 36
Manzanares-Martínez, J., 30
McGinnis, S.P., 1
Meeks, E., 334
Merchant, T.P., 152, 368
Metzger, R., 242
Meyer, B.K., 139
Mizuta, S., 36
Moffat, H.K., 251
Musil, J., 104

Niklasson, G.A., 119
Njoroge, W., 82
Nyberg, T., 43

Oates, A.S., 110
Oh, J.T., 77
Olowolafe, J.O., 19

Pérez-Robles, J.F., 30
Park, G.-S., 7
Pingsheng, H., 67
Pons, M., 264

Que, W.X., 77

Ramírez-Bon, R., 30

Rau, I., 19
Ren, C.X., 53
Rodríguez, J., 119
Rodríguez-Clemente, R., 12

Saadoun, L., 12
Sadigh, B., 219
Sarychev, M.E., 211
Schafbauer, T., 307
Scharmann, A., 139
Shimogaki, Y., 176
Spitzer, A., 242
Stollenwerk, J., 139
Swann, C.P., 19

Tate, J., 134
Theiss, S.K., 219
Thiart, J.J., 275
Tian, J., 49
Trube, J., 139
Tsai, C.J., 72

Unruh, K.M., 19
U'Ren, G.D., 147
Usui, H., 22

Vigil, E., 12
Viljoen, H.J., 275

Wang, G., 116
Wang, H., 94
Wang, K.L., 147
Wang, W., 116
Wang, X., 94
Wang, Z., 201
Weihua, G., 67
Weis, H., 82
Weixing, L., 67
Werner, C., 242
Wessels, B.W., 126
Wilson, I.H., 53
Wong, S.P., 53
Wu, S.K., 61
Wuttig, M., 82

PII: S0040-6090(00)00929-9

Xi, S., 129
Xu, J., 116

Yamaguchi, I., 36
Yang, G.-M., 7
Yu, K.H., 72
Yu, Y.H., 53

Zeng, G., 129
Zhang, F., 94
Zhao, J., 110
Zheng, Z., 94
Zhitnikov, Y.V., 211
Zhou, Y., 77
Zhu, J., 219
Zou, S.C., 53
Zumeta, I., 12

ELSEVIER

Thin Solid Films 365 (2000) 378–382

thin solid films

www.elsevier.com/locate/tsf

Subject Index of Volume 365

α-Al_2O_3 substrates
Effects of temperature and atmosphere on the epitaxial growth of hematite (α–Fe_2O_3) films on the *R*-, *A*- and *C*-planes of sapphire (α–Al_2O_3) by coating-pyrolysis process, 36
α-Fe_2O_3 thin film
Effects of temperature and atmosphere on the epitaxial growth of hematite (α–Fe_2O_3) films on the *R*-, *A*- and *C*-planes of sapphire (α–Al_2O_3) by coating-pyrolysis process
Absorption behaviour
Adsorption of precursor molecules in the CVD process of (Ba;Sr)titanate simulated by ab-initio calculations, 242
Adsorption
Two dimensional array of magnetoferritin on quartz surface, 99
Annealing
Stress evolution of Ni/Pd/Si reaction system under isochronal annealing, 72
Anti-reflection coating
Better thermochromic glazing of windows with anti-reflection coating, 5
Ar pressure effect on peak intensity
Composition control of r.f.-sputtered $Ti_{50}Ni_{40}Cu_{10}$ thin films using optical emission spectroscopy, 61
Atomic scale model
Atomic scale models of ion implantation and dopant diffusion in silicon, 219
Auger electron spectroscopy
Compositional and structural studies of DC magnetron sputtered SiC films on Si(111), 53

Bismuth titanate niobate $Bi_7Ti_4NbO_{21}$
Ferroelectric properties of bismuth titanate niobate $Bi_7Ti_4NbO_{21}$ thin film, 58
$BiVO_4$ thin film
$BiVO_4$ thin film preparation by metalorganic decomposition, 90
Borane
A chemical mechanism for in situ boron doping during silicon chemical vapor deposition, 231

C-axis orientation
C-axis oriented sol–gel derived $LiNb_{1-x}Ta_xO_3$ thin films on Si(111) substrates, 77
Characterization
Study of ferric oxide nanoparticles tris-(2,4-di-t-amylphenoxy)-(8-quinolinolyl) copper phthalocyanine composite LB film, 129
Chemical composition
Chemical composition and structure of titanium oxide films deposited on LTI-carbon by IBED, 94
Chemical vapor deposition
Characterization of SnO_2 films on glass by transmission electron microscopy, 7
Macro/microcavity method and its application in modeling chemical vapor deposition reaction systems, 176
Adsorption of precursor molecules in the CVD process of (Ba;Sr)titanate simulated by ab-initio calculations, 242
Chemical kinetics in chemical vapor deposition: growth of silicon dioxide from tetraethoxysilane (TEOS), 251
Chemical vapor deposition and morphology problems, 275
Computational modeling of transport phenomena and detailed chemistry in chemical vapor deposition – a benchmark solution, 294
Multiple scale integrated modeling of deposition processes, 368
Chemical vapor deposition simulation
A chemical mechanism for in situ boron doping during silicon chemical vapor deposition, 231
Coatings
Superhard nanocomposite $Ti_{1-x}Al_xN$ films prepared by magnetron sputtering, 104
Coating-pyrolysis process
Effects of temperature and atmosphere on the epitaxial growth of hematite (α–Fe_2O_3) films on the *R*-, *A*- and *C*-planes of sapphire (α–Al_2O_3) by coating-pyrolysis process, 36
Colloidal particles
Stabilization of copper-based colloidal particles in sol–gel SiO_2 thin films, 30
Composite LB film
Study of ferric oxide nanoparticles tris-(2,4-di-t-amylphenoxy)-(8-quinolinolyl) copper phthalocyanine composite LB film, 129
Copper
Stabilization of copper-based colloidal particles in sol–gel SiO_2 thin films, 30
Copper-based colloidal particles
Stabilization of copper-based colloidal particles in sol–gel SiO_2 thin films, 30
Copper phthalocyanine derivative
Study of ferric oxide nanoparticles tris-(2,4-di-t-amylphenoxy)-(8-quinolinolyl) copper phthalocyanine composite LB film, 129
Corrosion
Effect of cracks in TiN anti-reflection coating layers on early via electromigration failure, 110
Crystal growth
Lattice Monte Carlo models of thin film deposition, 189

PII: S0040-6090(00)00909-3

Cuprous oxides
Stabilization of copper-based colloidal particles in sol–gel SiO_2 thin films, 30

DC magnetron sputtering
Compositional and structural studies of DC magnetron sputtered SiC films on Si(111), 53
Deposition
Topography simulation for the virtual wafer fab, 152
Deposition process
TiO_2 thin film deposition from solution using microwave heating, 12
Polymeric film deposition by ionization-assisted method for optical and optoelectronic applications, 22
Dichlorosilane
A chemical mechanism for in situ boron doping during silicon chemical vapor deposition, 231
Dopant diffusion
Atomic scale models of ion implantation and dopant diffusion in silicon, 219

Electrical properties and measurements
Dependence of the electrical and optical behaviour of ITO–silver–ITO multilayers on the silver properties, 139
Electroluminescence
Synthesis and characterization of some ZnS-based thin film phosphors for electroluminescent device applications, 134
Electromigration
Effect of cracks in TiN anti-reflection coating layers on early via electromigration failure, 110
A new, general model for mechanical stress evolution during electromigration, 211
Embedded atom method
A new, general model for mechanical stress evolution during electromigration, 211
Energy minimization
Modeling Cu thin film growth, 201
Epitaxy
Effects of temperature and atmosphere on the epitaxial growth of hematite (α–Fe_2O_3) films on the *R*-, *A*- and *C*-planes of sapphire (α–Al_2O_3) by coating-pyrolysis process, 36
Er:$BaTiO_3$
Guided wave absorption and fluorescence in epitaxial Er:$BaTiO_3$ on MgO, 126
Etch
Topography simulation for the virtual wafer fab, 152
Evaporation
Synthesis and characterization of some ZnS-based thin film phosphors for electroluminescent device applications, 134

Faceting
Influence of misfit strain on {311} facet development in selective epitaxial growth of $Si_{1-x}Ge_x$/Si(100) grown by gas-source molecular beam epitaxy, 147
Ferric oxide nanoparticles
Study of ferric oxide nanoparticles tris-(2,4-di-t-amylphenoxy)-(8-quinolinolyl) copper phthalocyanine composite LB film, 129
Ferroelectric
Ferroelectric properties of bismuth titanate niobate $Bi_7Ti_4NbO_{21}$ thin film, 58
Fluorescence
Guided wave absorption and fluorescence in epitaxial Er:$BaTiO_3$ on MgO, 126

GeO_2
Physical properties of thin GeO_2 films produced by reactive DC magnetron sputtering, 82

Hardness
Superhard nanocomposite $Ti_{1-x}Al_xN$ films prepared by magnetron sputtering, 104
Heterostructures
Influence of misfit strain on {311} facet development in selective epitaxial growth of $Si_{1-x}Ge_x$/Si(100) grown by gas-source molecular beam epitaxy, 147

Indium tin oxide
Second harmonic generation investigation of indium tin oxide thin films, 116
Dependence of the electrical and optical behaviour of ITO–silver–ITO multilayers on the silver properties, 139
Ion beam enhanced deposition
Chemical composition and structure of titanium oxide films deposited on LTI-carbon by IBED, 94
Ion implantation
Atomic scale models of ion implantation and dopant diffusion in silicon, 219

Langmuir–Blodgett films
LB films formed from arachidic acid monolayers on an aqueous solution of a ruthenium(II) complex, 67
Lattice Monte Carlo models
Lattice Monte Carlo models of thin film deposition, 189
$LiNb_{1-x}Ta_xO_3$
C-axis oriented sol–gel derived $LiNb_{1-x}Ta_xO_3$ thin films on Si(111) substrates, 77
Local thermochemical equilibrium
Combined thermodynamic and mass transport modeling for material processing from the vapor phase, 264
Luminescence
The effect of electric field on the photoluminescence and absorption spectra of porous silicon, 1
LB films formed from arachidic acid monolayers on an aqueous solution of a ruthenium(II) complex, 67
Guided wave absorption and fluorescence in epitaxial Er:$BaTiO_3$ on MgO, 126
Luminous transmittance
Better thermochromic glazing of windows with anti-reflection coating, 5

Macro/microcavity method
Macro/microcavity method and its application in modeling chemical vapor deposition reaction systems, 176
Mechanical stress evolution
A new, general model for mechanical stress evolution during electromigration, 211
Mechanism
A chemical mechanism for in situ boron doping during silicon chemical vapor deposition, 231

Metalorganic decomposition
$BiVO_4$ thin film preparation by metalorganic decomposition, 90
Microelectronics
Chemical kinetics in chemical vapor deposition: growth of silicon dioxide from tetraethoxysilane (TEOS), 251
Modeling plasma chemistry for microelectronics manufacturing, 334
Model-based controller
Model-based control in rapid thermal processing, 322
Molecular beam, epitaxy
Influence of misfit strain on {311} facet development in selective epitaxial growth of $Si_{1-x}Ge_x$/Si(100) grown by gas-source molecular beam epitaxy, 147
Molecular dynamics
Modeling Cu thin film growth, 201
Monte Carlo methods
Modeling Cu thin film growth, 201
Multilayers
Dependence of the electrical and optical behaviour of ITO–silver–ITO multilayers on the silver properties, 139

Nanostructures
The effect of electric field on the photoluminescence and absorption spectra of porous silicon, 1
Two dimensional array of magnetoferritin on quartz surface, 99
Nickel
Stress evolution of Ni/Pd/Si reaction system under isochronal annealing, 72
Non-linear optical anisotropy
Second harmonic generation investigation of indium tin oxide thin films, 116
Numerical model
Modeling plasma chemistry for microelectronics manufacturing, 334

Optical coatings
Thickness dependence of the optical properties of sputter deposited Ti oxide films, 119
Optical properties
Physical properties of thin GeO_2 films produced by reactive DC magnetron sputtering, 82
Thickness dependence of the optical properties of sputter deposited Ti oxide films, 119
Dependence of the electrical and optical behaviour of ITO–silver–ITO multilayers on the silver properties, 139
Optical spectroscopy
Composition control of r.f.-sputtered $Ti_{50}Ni_{40}Cu_{10}$ thin films using optical emission spectroscopy, 61
Optical spectroscopy Sol–gel
Stabilization of copper-based colloidal particles in sol–gel SiO_2 thin films, 30
Optoelectronic devices
The effect of electric field on the photoluminescence and absorption spectra of porous silicon, 1
Polymeric film deposition by ionization-assisted method for optical and optoelectronic applications, 22
Organic semiconductors
Polymeric film deposition by ionization-assisted method for optical and optoelectronic applications, 22

Perturbation growth
Chemical vapor deposition and morphology problems, 275
Phase transition
Physical properties of thin GeO_2 films produced by reactive DC magnetron sputtering, 82
Planar growth
Chemical vapor deposition and morphology problems, 275
Plasma chemistry
Modeling plasma chemistry for microelectronics manufacturing, 334
Plasma etching reactor
Modeling and simulation of plasma etching reactors for microelectronics, 348
Plasma modeling
Modeling and simulation of plasma etching reactors for microelectronics, 348
Plasma processes
Topography simulation for the virtual wafer fab, 152
Plasma simulation
Modeling and simulation of plasma etching reactors for microelectronics, 348
Polyamide
Ni–Cr selective surface based on polyamide substrate, 49
Polymers
Polymeric film deposition by ionization-assisted method for optical and optoelectronic applications, 22
Precursor molecules
Adsorption of precursor molecules in the CVD process of (Ba;Sr)titanate simulated by ab-initio calculations, 242
Processor
Modeling plasma chemistry for microelectronics manufacturing, 334
Pulsed DC
Frequency response in pulsed DC reactive sputtering processes, 43

Quantum chemistry predictions
A chemical mechanism for in situ boron doping during silicon chemical vapor deposition, 231
Quantum effects
The effect of electric field on the photoluminescence and absorption spectra of porous silicon, 1

Raman microprobe
$BiVO_4$ thin film preparation by metalorganic decomposition, 90
Rapid thermal chemical vapour deposition
Thermal modelling of RTP and RTCVD processes, 307
Rapid thermal processing
C-axis oriented sol–gel derived $LiNb_{1-x}Ta_xO_3$ thin films on Si(111) substrates, 77
Thermal modelling of RTP and RTCVD processes, 307
Model-based control in rapid thermal processing, 322
Reaction scheme
Macro/microcavity method and its application in modeling chemical vapor deposition reaction systems, 176
Reactive sputtering
Frequency response in pulsed DC reactive sputtering processes, 43
Reactive DC-magnetron sputtering

Physical properties of thin GeO_2 films produced by reactive DC magnetron sputtering, 82
Reflow
Topography simulation for the virtual wafer fab, 152
Ruthenium complex
LB films formed from arachidic acid monolayers on an aqueous solution of a ruthenium(II) complex, 67
Rutherford backscattering spectroscopy
Compositional and structural studies of DC magnetron sputtered SiC films on Si(111), 53

Scanning electron microscopy
Two dimensional array of magnetoferritin on quartz surface, 99
Second harmonic generation
Second harmonic generation investigation of indium tin oxide thin films, 116
Semiconductors
Effect of cracks in TiN anti-reflection coating layers on early via electromigration failure, 110
Sensitivity analysis
A chemical mechanism for in situ boron doping during silicon chemical vapor deposition, 231
SiC films
Compositional and structural studies of DC magnetron sputtered SiC films on Si(111), 53
SiGe
Influence of misfit strain on {311} facet development in selective epitaxial growth of $Si_{1-x}Ge_x$/Si(100) grown by gas-source molecular beam epitaxy, 147
Silicide
Stress evolution of Ni/Pd/Si reaction system under isochronal annealing, 72
Silicon
Atomic scale models of ion implantation and dopant diffusion in silicon, 219
SiO_2 thin films
Stabilization of copper-based colloidal particles in sol–gel SiO_2 thin films, 30
SnO_2 films
Characterization of SnO_2 films on glass by transmission electron microscopy, 7
Sol–gel
Ferroelectric properties of bismuth titanate niobate $Bi_7Ti_4NbO_{21}$ thin film, 58
Sol–gel chemistry
C-axis oriented sol–gel derived $LiNb_{1-x}Ta_xO_3$ thin films on Si(111) substrates, 77
Solar selective surface
Ni–Cr selective surface based on polyamide substrate, 49
Spin coating process
Characterization of SnO_2 films on glass by transmission electron microscopy, 7
Sputtering
Effect of composition on thermal stability and electrical resistivity of Ta–Si–N films, 19
Ni–Cr selective surface based on polyamide substrate, 49
Composition control of r.f.-sputtered $Ti_{50}Ni_{40}Cu_{10}$ thin films using optical emission spectroscopy, 61
Superhard nanocomposite $Ti_{1-x}Al_xN$ films prepared by magnetron sputtering, 104
Thickness dependence of the optical properties of sputter deposited Ti oxide films, 119
Stress
Stress evolution of Ni/Pd/Si reaction system under isochronal annealing, 72
Structural properties
Effect of composition on thermal stability and electrical resistivity of Ta–Si–N films, 19
Superhard nanocomposite $Ti_{1-x}Al_xN$ films prepared by magnetron sputtering, 104
Structure
Chemical composition and structure of titanium oxide films deposited on LTI-carbon by IBED, 94
Surface composition
Synthesis and characterization of some ZnS-based thin film phosphors for electroluminescent device applications, 134
Surface structure
Two dimensional array of magnetoferritin on quartz surface, 99
Surface-to-volume ratio
Macro/microcavity method and its application in modeling chemical vapor deposition reaction systems, 176

Ta–Si–N
Effect of composition on thermal stability and electrical resistivity of Ta–Si–N films, 19
Temperature control algorithms
Model-based control in rapid thermal processing, 322
Tetraethoxysilane
Multiple scale integrated modeling of deposition processes, 368
Tetraethylsiloxane
Chemical kinetics in chemical vapor deposition: growth of silicon dioxide from tetraethoxysilane (TEOS), 251
Thermal modelling
Thermal modelling of RTP and RTCVD processes, 307
Thermal processes
Topography simulation for the virtual wafer fab, 152
Thermal stability
Effect of composition on thermal stability and electrical resistivity of Ta–Si–N films, 19
Thermochromism
Better thermochromic glazing of windows with anti-reflection coating, 5
Thermodynamic analysis
Combined thermodynamic and mass transport modeling for material processing from the vapor phase, 264
Thin films
Ferroelectric properties of bismuth titanate niobate $Bi_7Ti_4NbO_{21}$ thin film, 58
C-axis oriented sol–gel derived $LiNb_{1-x}Ta_xO_3$ thin films on Si(111) substrates, 77
Thin film deposition
Lattice Monte Carlo models of thin film deposition, 189
Thin film growth
Modeling Cu thin film growth, 201
$Ti_{50}Ni_{40}Cu_{10}$ shape memory alloy
Composition control of r.f.-sputtered $Ti_{50}Ni_{40}Cu_{10}$ thin films using optical emission spectroscopy, 61
Titanium oxide
TiO_2 thin film deposition from solution using microwave heating, 12

Thickness dependence of the optical properties of sputter deposited Ti oxide films, 119
Titanium oxide film
Chemical composition and structure of titanium oxide films deposited on LTI-carbon by IBED, 94
Topography simulation
Topography simulation for the virtual wafer fab, 152
Transmission electron microscopy
Characterization of SnO_2 films on glass by transmission electron microscopy, 7
Transport phenomena
Computational modeling of transport phenomena and detailed chemistry in chemical vapor deposition – a benchmark solution, 294
Trapping
Atomic scale models of ion implantation and dopant diffusion in silicon, 219
Tungsten
Effect of cracks in TiN anti-reflection coating layers on early via electromigration failure, 110

Vanadium dioxide
Better thermochromic glazing of windows with anti-reflection coating, 5
Vapor phase process
Combined thermodynamic and mass transport modeling for material processing from the vapor phase, 264

Window glazing
Better thermochromic glazing of windows with anti-reflection coating, 5

X-ray diffraction
Compositional and structural studies of DC magnetron sputtered SiC films on Si(111), 53
LB films formed from arachidic acid monolayers on an aqueous solution of a ruthenium(II) complex, 67
C-axis oriented sol–gel derived $LiNb_{1-x}Ta_xO_3$ thin films on Si(111) substrates, 77
Physical properties of thin GeO_2 films produced by reactive DC magnetron sputtering, 82

ZnS-based thin films
Synthesis and characterization of some ZnS-based thin film phosphors for electroluminescent device applications, 134